Repetition: Sputter Yield



<n> = mean number of particles emitted per impingement n⁺ = number of impinging ions

Y is dependent on several parameters of the ions and of the target material.



Repetition: Energy of Ejected Particles



The energy distribution of sputtered particles is significantly different from that of thermally evaporated ones.

Repetition: Angular Distribution at Emission



$$n(\alpha) \propto \cos^{n} \alpha$$

 $n \leq 1 \quad \text{E} < 1 \text{ keV}$
 $n > 1 \quad \text{E} > 1 \text{ keV}$

Repetition: Sputtering of Alloys



In the case of the homogenous distribution of the constituents the vapor composition is (after a transient regime) identical to the target composition.

Repetition: Reaktive Processes (TiN)

Pressure in the chamber in dependence on the N₂- flow:



point A would be the optimum working condition

Gas Phase Transport



Modification of energy- and angular distribution of the coating material during the transport from source to substrate.

- Deposition material
- Working gas, neutral or reactive

Film Particle Trespasses Gas Phase



Per collision the particle suffers a mean energy loss ΔE and a mean change of the angle $\Delta \phi$.

Mean Energy Loss I

Initial condition: particle 1 at rest, particle 2 moves. Wanted: energy loss of particle 2.

$$\left\langle \frac{E'}{E} \right\rangle = 1 - \frac{1}{2} \cdot \frac{4 \cdot \mu}{\left(1 + \mu\right)^2}, \quad \mu = \frac{m_1}{m_2}, \quad \left\langle \Delta E \right\rangle \approx E \cdot \left(1 - \left\langle \frac{E'}{E} \right\rangle \right)$$

E ... Energy particle 2 before collision E' ... Energy particle 2 after collision

Light working gas: $\mu = 0.1 \Rightarrow \langle E'/E \rangle = 0.83$ Equal masses: $\mu = 1 \Rightarrow \langle E'/E \rangle = 0.5$

Heavy working gas: $\mu = 10 \Longrightarrow \langle E'/E \rangle = 0.83$

Mean Energy Loss II

Situation after 5 Collisions:

Light working gas: $\mu = 0.1 \Rightarrow (\langle E'/E \rangle)^5 = 0.4$ Equal masses: $\mu = 1 \Rightarrow (\langle E'/E \rangle)^5 = 0.03$ Heavy working gas: $\mu = 0.1 \Rightarrow (\langle E'/E \rangle)^5 = 0.4$

For more realistic collision processes there are energy dependent collisional cross sections. The slower a particle is, the larger is it's cross section. Furthermore at a certain point the velocity distribution if the gas atoms has to be taken into account.

Mean Scattering Angle I

Mean scattering angle θ of particle 2:

$$\left\langle \cos \varphi \right\rangle = 1 - \frac{\mu^2}{3}, \quad \mu = \frac{m_1}{m_2} < 1$$
$$\left\langle \cos \varphi \right\rangle = \frac{2}{3 \cdot \mu}, \quad \mu = \frac{m_1}{m_2} > 1$$

Light working gas: $\mu = 0.1 \Rightarrow \langle \phi \rangle = 4.6^{\circ}$ Equal masses: $\mu = 1 \Rightarrow \langle \phi \rangle = 48.2^{\circ}$ Heavy working gas: $\mu = 10 \Rightarrow \langle \phi \rangle = 86.2^{\circ}$

Mean Scattering Angle II

Number f collisions n, to cover 360° (complete loss of directional information):

Light working gas: $\mu = 0.1 \Rightarrow \langle \phi \rangle = 4.6^{\circ}$ n = 79Equal masses: $\mu = 1 \Rightarrow \langle \phi \rangle = 48.2^{\circ}$

Heavy working gas:

$$n = 8$$

$$\mu = 10 \Longrightarrow \langle \phi \rangle = 86.2^{\circ}$$

$$n = 5$$

Summary Gas Phase Scattering

As a result of collisions in the gas phase two limiting cases can be distinguished:



Elementary Steps of Film Deposition



Surface Types I

Face centered cubic







(100)

(110)

000000 $\circ \circ \circ \circ \circ \circ \circ \circ ^{a}$ 0000000 0000000 $a\sqrt{2}$

(111)

Surface Types II

Body centered cubic







(100)

(110)

(111)







Determination of Potential Energy Surfaces



Topmost Atomic Layers (Side View)

Elementary Potential Energy Surfaces





(110)



(111)

More Complex Surface Geometries

Stepped surface – Ehrlich Schwöbel barrier



Binding Energies

Important binding energies



Elementary Processes: Phonon Oscillations





Desoprtion frequency:



$$E_{Des} \cong 1 - 3eV$$

Elementary Processes: Surface Diffusion



Diffusion frequency:



 $E_{\text{Diff}} \cong 0.1 - 0.8 \text{eV}$

Surface Diffusion: Random Walk

Pvthagoras:



$$l^{2} = \left(\sum_{i=1}^{n_{x}} x_{i}\right)^{2} + \left(\sum_{i=1}^{n_{y}} y_{i}\right)^{2} \qquad x_{i}, y_{i} = \pm a$$

$$l^{2} = \left(\sum_{i=1}^{n_{x}} x_{i} \sum_{j=1}^{n_{x}} x_{j}\right) + \left(\sum_{i=1}^{n_{x}} y_{i} \sum_{j=1}^{n_{x}} y_{j}\right)$$

$$\left\langle l^{2} \right\rangle = \left\langle \left(\sum x_{i} \sum x_{j}\right) \right\rangle + \left\langle \left(\sum y_{i} \sum y_{j}\right) \right\rangle =$$

$$= \left\langle \sum_{i=1}^{n_{x}} x_{i}^{2} \right\rangle + \left\langle \sum_{i=1}^{n_{y}} y_{i}^{2} \right\rangle = (n_{x} + n_{y}) \cdot a^{2} = N \cdot a^{2}$$

1...effective distance travelled by particle

$$\langle l^2 \rangle = \mathbf{N} \cdot \mathbf{a}^2$$

Surface Diffusion: Diffusion Coefficient

$$\begin{pmatrix} 1^{2} \\ \end{pmatrix} = N \cdot a^{2}$$

$$D = v_{0} \cdot a^{2} \cdot e^{-\frac{E_{\text{Diff}}}{k_{B}T_{S}}} [m^{2}s^{-1}]$$

$$V_{\text{Diff}} = v_{0} \cdot e^{-\frac{E_{\text{Diff}}}{k_{B}T_{S}}}$$

$$Einstein-relation:$$

$$\begin{pmatrix} 1 \\ \end{pmatrix} \cong \sqrt{D\tau}[m]$$

$$r = \text{Diffusion time}$$



Lattice vibrations:

$$v_0 \cong 5 \cdot 10^{12} \,\mathrm{Hz}$$

Surface diffusion:



$T_{S} = 300 \text{ K}$ $k_{B} = 1,38.10^{-23} \text{J/K}$

$$\begin{split} & \mathsf{E}_{\mathsf{Diff}} = 0,2 \; eV{=}3,2.10^{-20} \; \mathsf{J} \\ & \nu_{\mathsf{Diff}} = 2,2.10^9 \; \mathsf{Hz} \\ & \tau_{\mathsf{Diff}} = \nu_{\mathsf{Diff}}{}^{-1}{=}\; 0.5 \; \mathsf{ns} \end{split}$$

Desorption:

$$v_{\text{Des}} = v_0 \cdot e^{-\frac{E_{\text{Des}}}{k_B T_S}}$$

 $E_{Des} = 2 \text{ eV} = 3,2.10^{-19} \text{ J}$ $v_{Des} = 1,2.10^{-21} \text{ Hz(!)}$ $\tau_{Des} = v_{Des}^{-1} = 10^{13} \text{ a}$

Time Scales II



Important phenomena happen on extremely different time scales!

Condensation Regimes

 Complete condensation:
 Each impinging particle remains on the surface because of the extremely low desorption frequency. Prerequisite: T_s <

 Incomplete condensation:
 Particles can desorb, an adsorption/desorption-equilibrium is created ein (see later).
 Prerequisite: T_s >